

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1-20. (Canceled)

21. (Currently Amended) A liquid immersion exposure apparatus that includes an exposure station and a measuring station and exposes a substrate via a liquid at the exposure station, comprising:

a plurality of movable members each of which that holds a substrate and is movable between the exposure station and the measuring station;

an optical member disposed at the exposure station which irradiates an exposure beam to the substrate held by a first one of the movable members at the exposure station; and

a measurement device positioned at the measuring station, which measures a second one of the movable members or a substrate held by the second movable member at the measuring station,

wherein a liquid is partially disposed on the second movable member or on the substrate held by the second movable member, at the measuring station.

22. (Previously Presented) The liquid immersion exposure apparatus according to claim 21, wherein the measurement at the measuring station is performed during the exposure at the exposure station.

23. (Previously Presented) The liquid immersion exposure apparatus according to claim 21, wherein the measuring station comprises a surface detection device that measures, via a liquid, a surface information of the substrate held by the second movable member.

24. (Previously Presented) The liquid immersion exposure apparatus according to claim 21, further comprising:

a member having a liquid contact surface substantially equivalent to the liquid contact surface of the optical member,

wherein a first immersion area is formed between the optical member and the substrate at the exposure station, and a second immersion area is formed between the contact member and the substrate at the measuring station.

25. (Previously Presented) The liquid immersion exposure apparatus according to claim 21, further comprising:

a measurement device that measures a force exerted by the liquid upon the second movable member or on the substrate held by the second movable member.

26. (Previously Presented) The liquid immersion exposure apparatus according to claim 25, wherein a surface position of the substrate at the exposure station is compensated based on the measurement result of the measurement device.

27. (Previously Presented) The liquid immersion exposure apparatus according to claim 25, wherein the measurement device measures the force exerted on the substrate at each of a plurality of positions, in a state in which the liquid is disposed on the second movable member or on the substrate held by the second movable member.

28. (Previously Presented) The liquid immersion exposure apparatus according to claim 21, wherein

a first surface information related to the substrate is obtained by performing a measurement in a state in which the liquid is disposed on the substrate, with the measurement device at the measuring station;

a second surface information related to the substrate is obtained by performing a measurement in a state in which the liquid is disposed on the substrate, with the measurement device at the exposure station; and

a compensation quantity that compensates the second surface information of

the substrate at the exposure station is determined based on the first information and second surface information.

29. (Previously Presented) The liquid immersion exposure apparatus according to claim 21, wherein a surface information of the substrate is obtained in accordance with the position of an immersion area in the surface direction of the substrate.

30. (Previously Presented) The liquid immersion exposure apparatus according to claim 21, wherein the measuring station comprises a first mark detection device that measures, via liquid, an alignment mark on the substrate held by the second movable member and also measures, via liquid, a fiducial mark provided on the second movable member.

31. (Previously Presented) The liquid immersion exposure apparatus according to claim 21, wherein a part of the each of a plurality of movable members that contacts with a liquid is provided with liquid repellency treatment.

32. (Previously Presented) The liquid immersion exposure apparatus according to claim 21, wherein each of a plurality of movable members has a surface that is substantially flush with the surface of the substrate held by the movable member around the circumference of the substrate.

33. (Previously Presented) The liquid immersion exposure apparatus according to claim 21, wherein the measurement is performed via the liquid.

34. (Previously Presented) The liquid immersion exposure apparatus according to claim 21, wherein the substrate on the first movable member that was measured at the measuring station is exposed at the exposure station.

35. (Currently Amended) An exposure method utilizing a liquid immersion exposure apparatus that includes an exposure station and a measuring station and exposes a substrate via a liquid at the exposure station, the method comprising:

holding a substrate by a plurality of movable members respectively, each of

the plurality of movable members is movable between the exposure station and the measuring station;

irradiating an exposure beam to the substrate held by a first one of the movable members of the plurality of movable members at the exposure station; and

measuring a second one of the movable members or a substrate held by the second movable member at the measuring station,

wherein a liquid is partially disposed on the second movable member or on the ~~substrate~~ substrate held by the second movable member, at the measuring station.

36. (Previously Presented) The method according to claim 35, wherein the measuring the second movable member or the substrate comprises measuring a surface information of the substrate via a liquid.

37. (Previously Presented) The method according to claim 35, further comprising:
providing a member having a liquid contact surface substantially equivalent to a liquid contact surface of an optical member that irradiates the exposure beam;

forming a first immersion area between the optical member and the substrate at the exposure station; and

forming a second immersion area between the member and the substrate at the measuring station.

38. (Previously Presented) The method according to claim 35, wherein the measurement at the measuring station is performed during the exposure at the exposure station.

39. (Previously Presented) The method according to claim 35, further comprising:
providing a liquid repellency treatment to a part of the each of the plurality of movable members that makes contact with a liquid.

40. (Previously Presented) The method according to claim 35, wherein each of a

plurality of movable members have a surface that is substantially flush with the surface of the substrate held by the movable member around the circumference of the substrate.

41. (Previously Presented) The method according to claim 35, wherein the measurement is performed via the liquid.

42. (Previously Presented) A liquid immersion exposure apparatus that includes an exposure station and a measuring station and exposes a substrate via a liquid at the exposure station, comprising:

a plurality of movable members each of which holds a substrate and is movable between the exposure station and the measuring station;

an optical member disposed at the exposure station which irradiates an exposure beam to the substrate held by a first one of the movable members at the exposure station;

a first liquid supply device that forms an immersion area on the substrate held by the first movable member at the exposure station; and

a second liquid supply device that forms an immersion area partially on a substrate held by a second one of the movable member at the measuring station.

43. (Previously Presented) A device fabricating method, the method comprising:
exposing a substrate with the liquid immersion exposure apparatus of claim 21; and
processing the exposed substrate to form the device.

44. (Previously Presented) A device fabricating method, the method comprising:
exposing a substrate with the liquid immersion exposure apparatus of claim 42; and
processing the exposed substrate to form the device.

45. (Previously Presented) A device fabricating method, the method comprising:

exposing a substrate with the exposure method of claim 35; and
processing the exposed substrate to form the device.